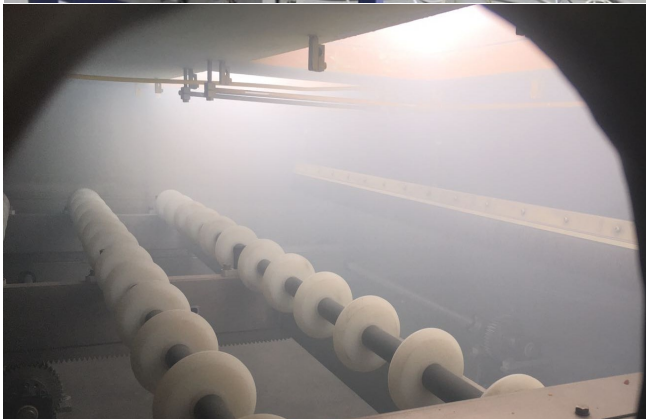
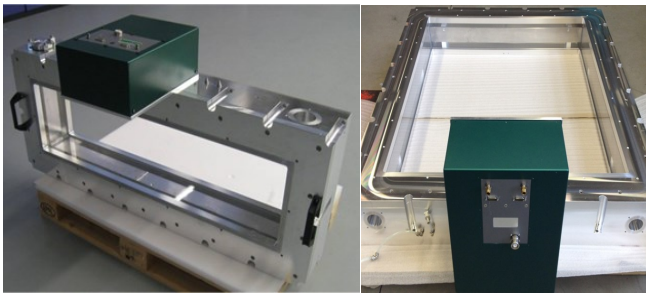
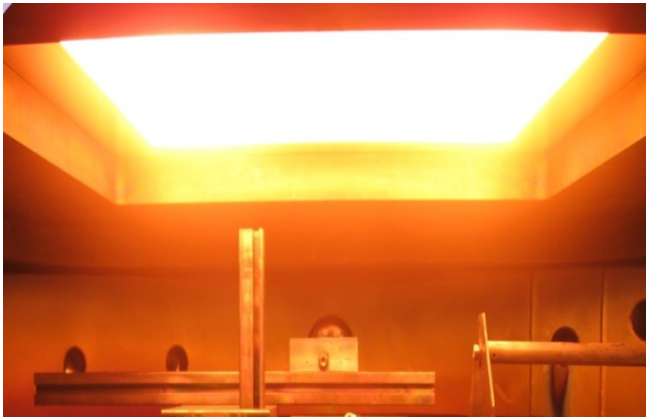


COPRA® LARGE AREA RF-ICP-Plasma Technology

PECVD- PVD Assist- Cleaning- Activation



The CCR COPRA Plasma Sources, a Radio Frequency powered Inductively Coupled Technology developed to deliver highest film quality and throughput performances for your future large area coating requirements.

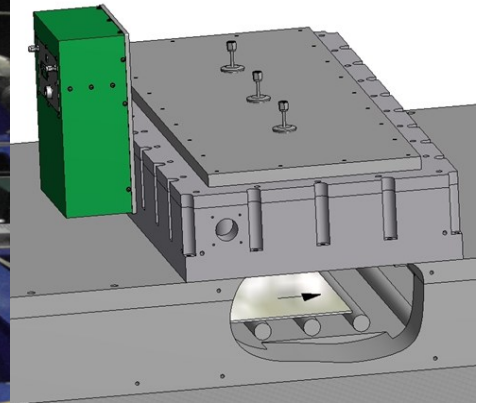
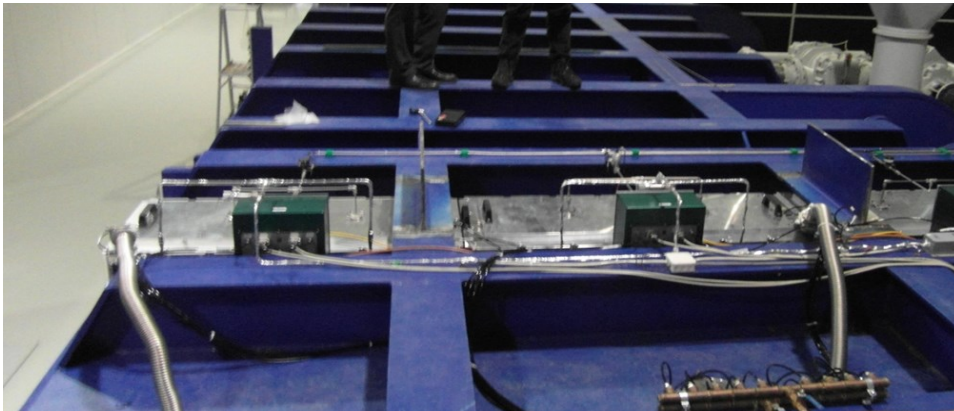
Scalability of COPRA RS

- RS-1000x400
- RS-850x850
- RS-950x900
- RS-500x500
- Custom size

*Dimensions in Plasma Opening (mm)

CCR COPRA Technology represent a state of the art Plasma Enhanced /Assisted Chemical Vapor Deposition solution.

Overcome the restriction in scalability of your metal oxide/nitride coatings! As a consequence of COPRA's highest ion current densities performance parameters paired with its adjustable specific process related controlled ion energy delivery features the CCR COPRA technology definitely paves the road for large area depositions.



3 Plasma sources mounted in line (2011)

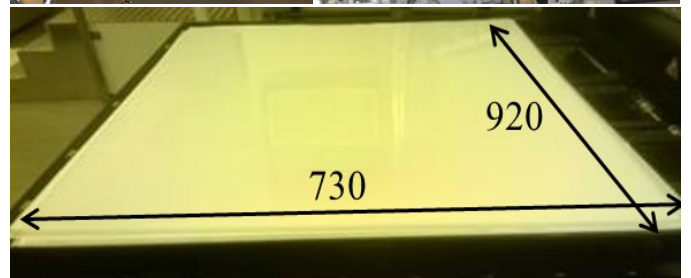
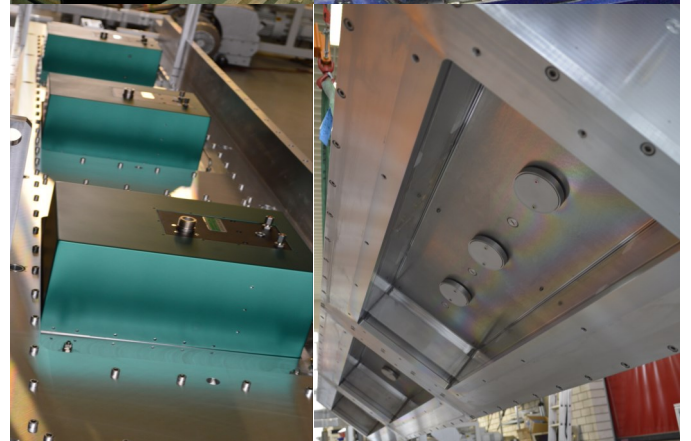
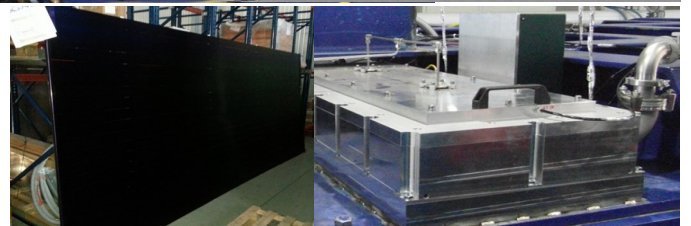
- SiO, SiN Al2O3, or other Large Area Solution for In line dynamic coating processes

High rate deposition due to

- High dissociation degree
- Plasma density up to 10^{11} cm^{-3}

Low temperature on substrate due to

- Low Ion energies $< 50\text{eV}$
- Ion density control independent from ion energy
- Quasi neutral plasma
- High compatibility with corrosive gases
- Low maintenance
- Long term stability of plasma properties as f.e. Ion Energy & Ion Current Density



CCR GmbH, Beschichtungstechnologie

Camp-Spich-Str. 3a

D-53842 Troisdorf

Tel.: +49 (0) 2241-93215-0

Fax.: +49 (0) 2241-93215-200

Email: contact@ccrtechnology.de

www.ccrtechnology.de